

ASML

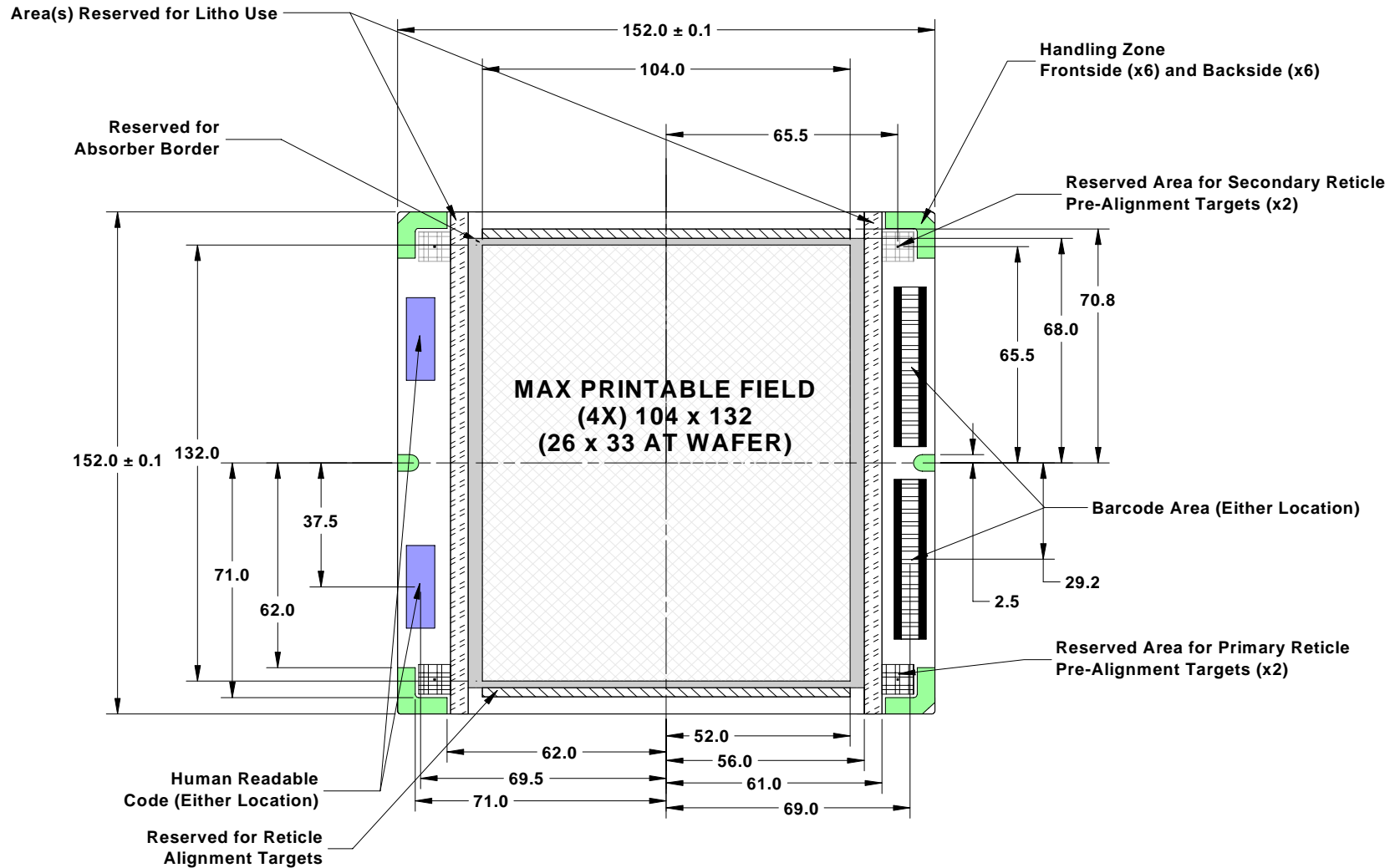
ASML Comments to SEMI Draft 3419



ASML

Changes to Layout of the EUVL Mask

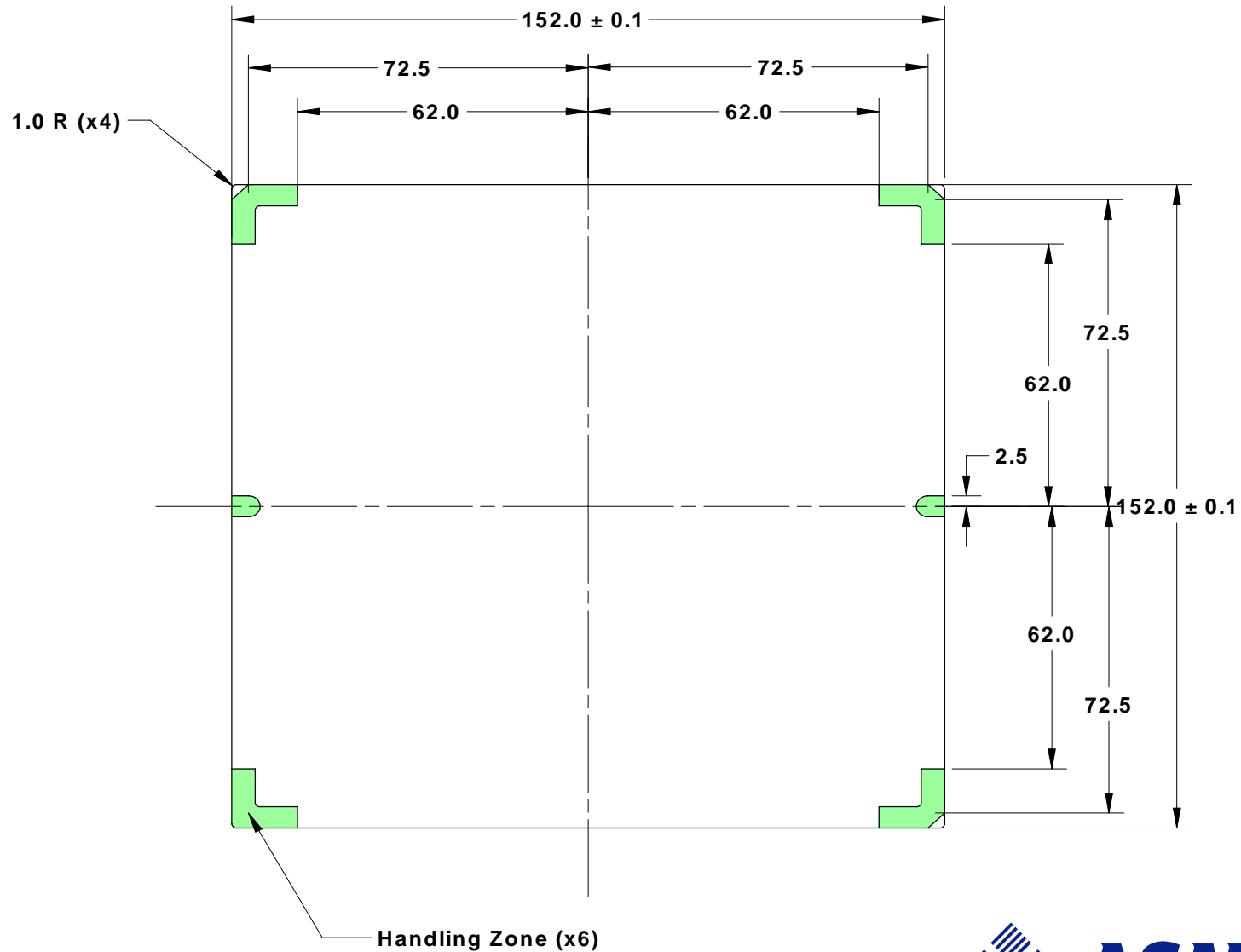
Revised Figure 1 - EUVL Mask Layout



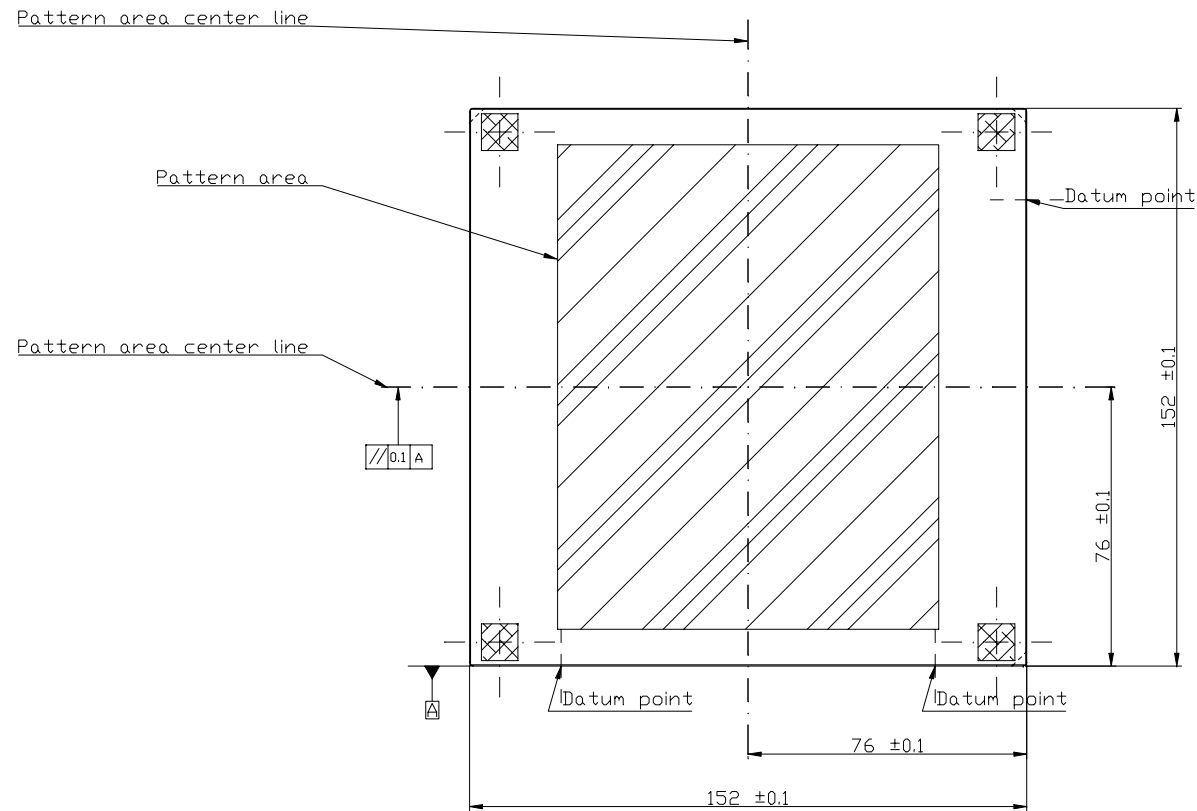
ALL DIMENSIONS IN MILLIMETERS



Added Figure: EUVL Mask Layout (Backside)

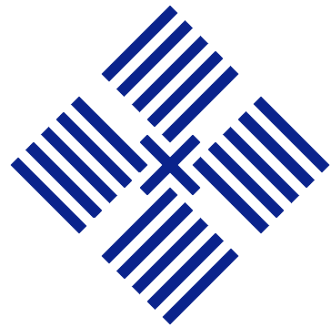


Added: Pattern Placement Accuracy Proposal: specify pattern placement accuracy in SEMI draft 3419



EUV reticle - pattern side view



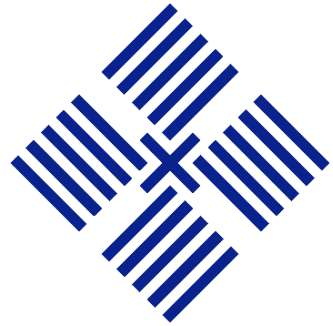


ASML

Changes to Chucking Section of 3419

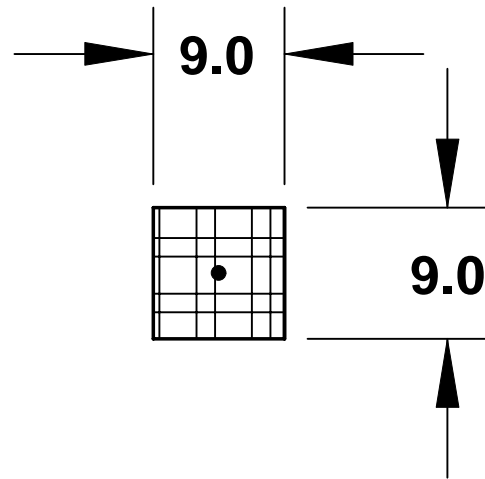
3419 Chucking Section Changes

- λ Table 4: ASML recommends deleting Period, Angle of sidewall and Pin Height parameters from the Table 4, since it is specific to the design of the chuck, and is only listed as “agreed to between supplier and user”
- λ Figure 5: ASML recommends deleting Figure 5, since Table 4 has been changed.
- λ ASML recommends adding a fourth parameter: foundation stiffness, which specifies the stiffness of the contact between the reticle and the chuck

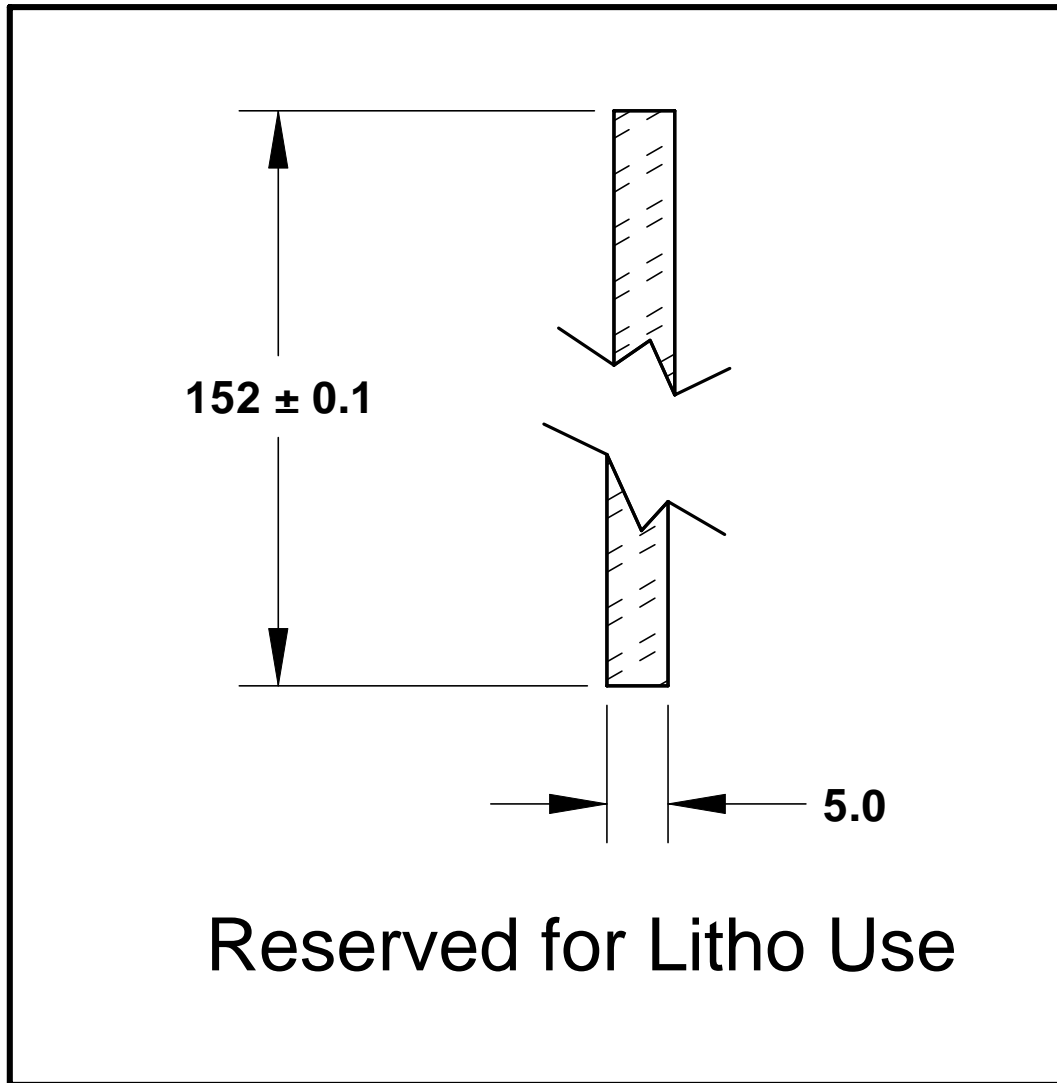


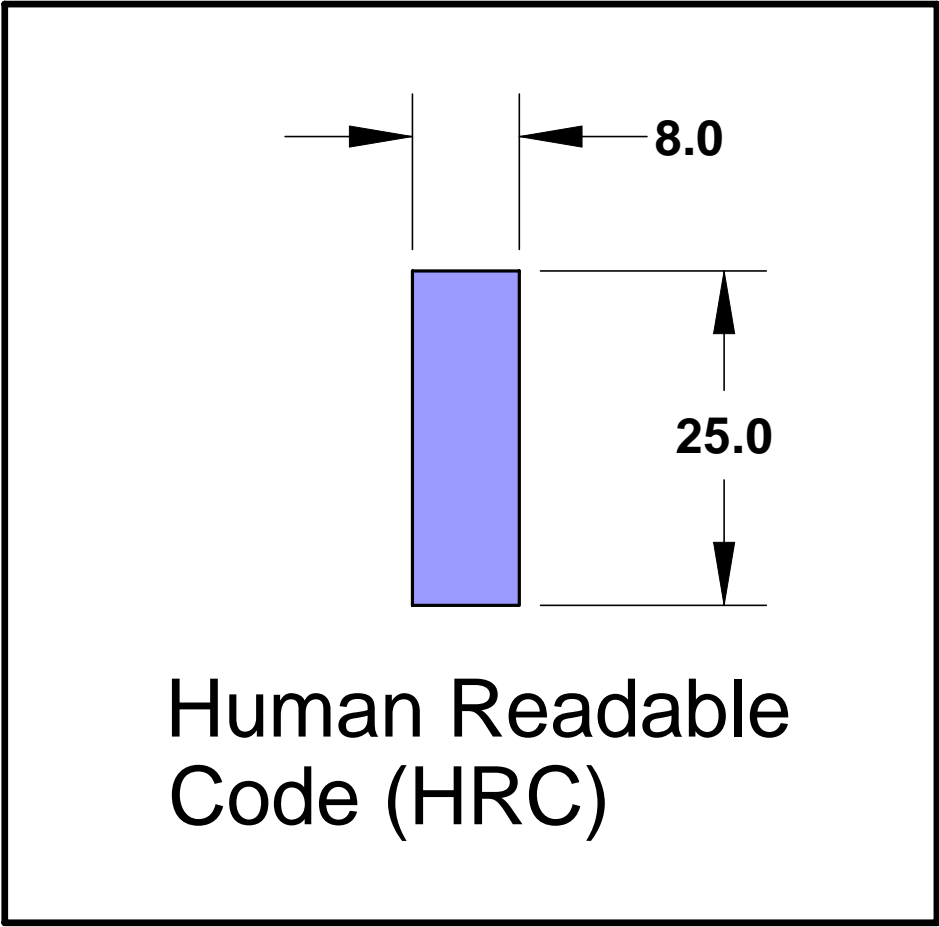
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Back Up Slides - Details of Features in Mask Layout (Figure 1)



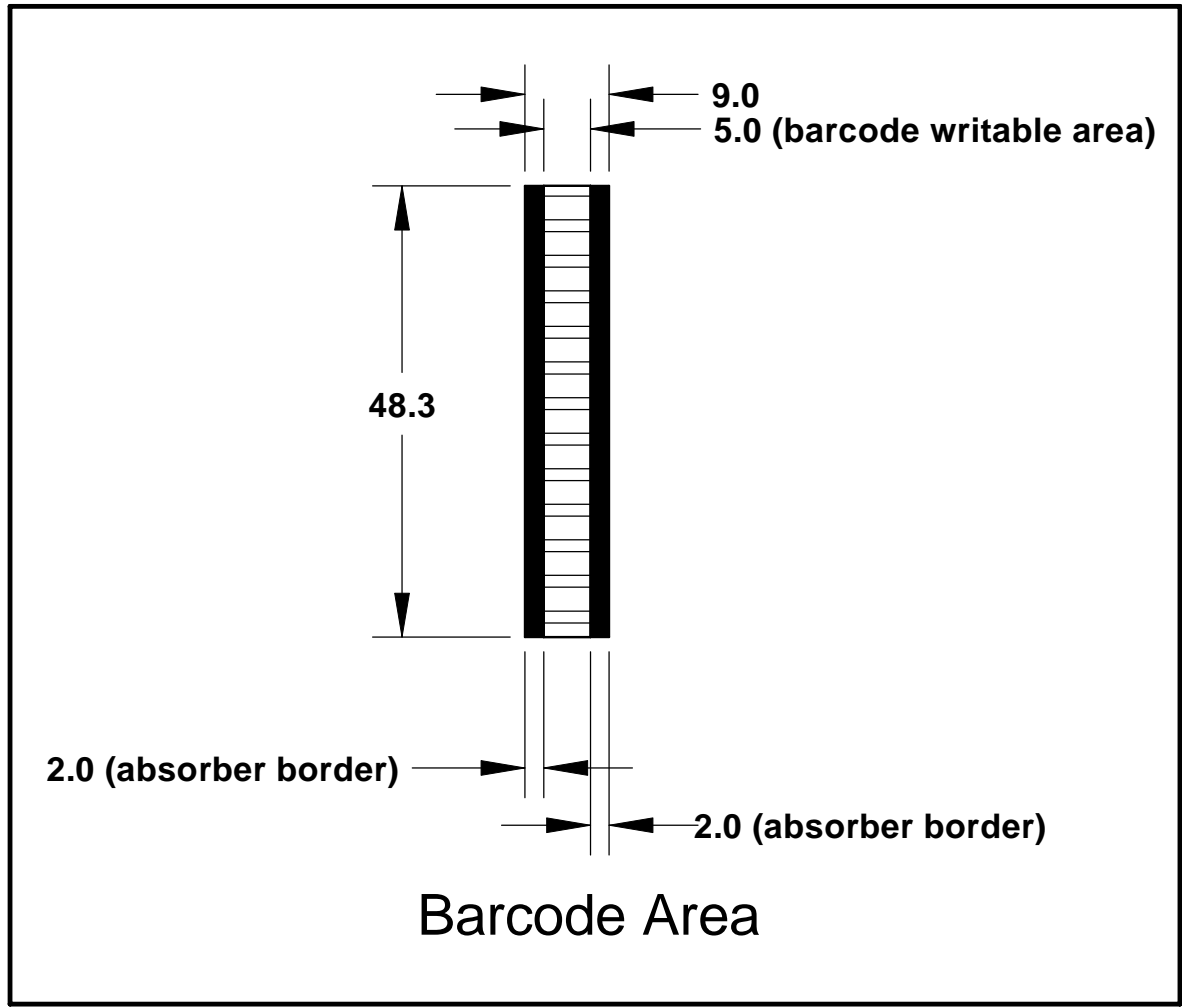
Pre-Alignment Targets





Human Readable
Code (HRC)





Barcode Area

